

# Time of flight sensors R&D

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TOF working group



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	Inner TOF	Outer TOF	Forward TOF
Radius (m)	0.19	0.85	0.15–1.5
z range (m)	−0.62–0.62	−2.79–2.79	4.05
Surface (m <sup>2</sup> )	1.5	30	14
Granularity (mm <sup>2</sup> )	1 × 1	5 × 5	1 × 1 to 5 × 5
Hit rate (kHz/cm <sup>2</sup> )	74	4	122
NIEL (1 MeV n <sub>eq</sub> /cm <sup>2</sup> ) / month	1.3 × 10 <sup>11</sup>	6.2 × 10 <sup>9</sup>	2.1 × 10 <sup>11</sup>
TID (rad) / month	4 × 10 <sup>3</sup>	2 × 10 <sup>2</sup>	6.6 × 10 <sup>3</sup>
Material budget (%X <sub>0</sub> )	1–3	1–3	1–3
Power density (mW/cm <sup>2</sup> )	50	50	50
Time resolution (ps)	20	20	20

Table 11: TOF specifications.

- Low Gain Avalanche Diodes (**LGADs**) readout by dedicated front-end chips have become a **workhorse** for **high resolution** silicon **timing** detectors for charged particles
- Typical **resolution** is 50 ps and can be improved with **thinner sensors**.
- ALICE3 **TOF** combines large area, coarse pixel sizes and moderate event rate: perfect case for monolithic **CMOS sensors with gain**...which are not yet “off the shelf”!
- Approach:
  - Study the timing **performance** of **conventional LGADs** with **reduced active thickness**
  - Develop **CMOS** sensors with **internal gain**



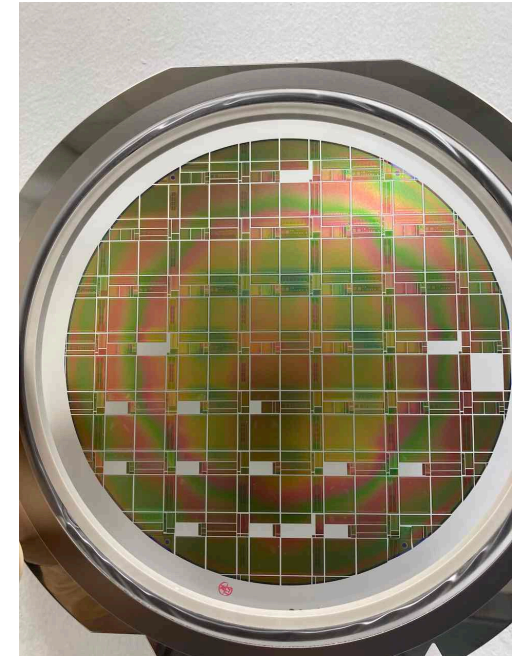
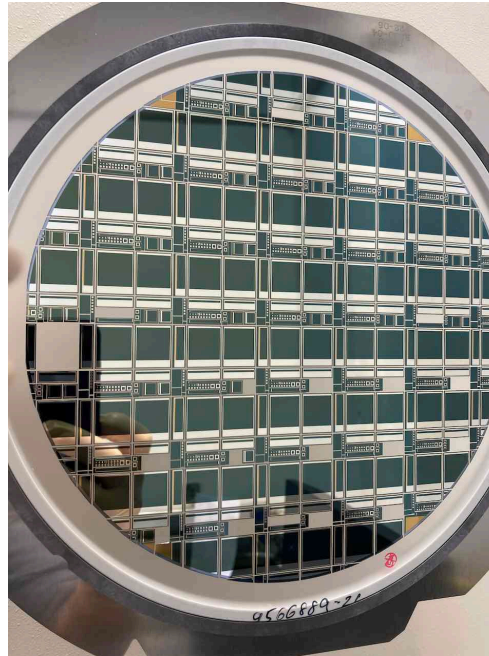
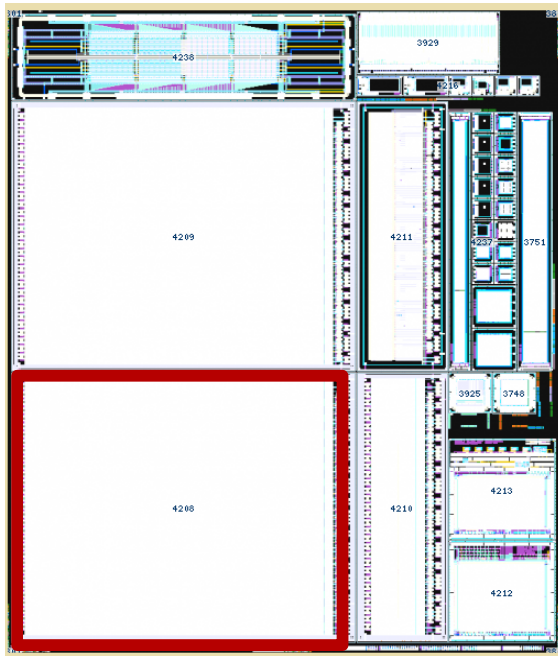
## Beam test results of 25 and 35 $\mu\text{m}$ thick FBK ultra-fast silicon detectors

F. Carnesecchi<sup>1,a</sup> , S. Strazzi<sup>2,b</sup>, A. Alici<sup>2</sup>, R. Arcidiacono<sup>4,6</sup>, G. Borghi<sup>7,9</sup>, M. Boscardin<sup>7,9</sup>, N. Cartiglia<sup>4</sup>, M. Centis Vignali<sup>7,9</sup>, D. Cavazza<sup>3</sup>, G. -F. Dalla Betta<sup>8,9</sup>, S. Durando<sup>5</sup>, M. Ferrero<sup>4</sup>, F. Ficorella<sup>7,9</sup>, O. Hammad Ali<sup>7,9</sup>, M. Mandurrino<sup>4</sup>, A. Margotti<sup>3</sup>, L. Menzio<sup>4,5</sup>, R. Nania<sup>3</sup>, L. Pancheri<sup>8,9</sup>, G. Paternoster<sup>7,9</sup>, G. Scioli<sup>2</sup>, F. Siviero<sup>4</sup>, V. Sola<sup>4,5</sup>, M. Tornago<sup>4,5</sup>, G. Vignola<sup>2</sup>

	Voltage applied	Gain	Time resolution
FBK25	120 V	$57 \pm 4$	$(25 \pm 3)$ ps
FBK35	240 V	$49 \pm 5$	$(22 \pm 2)$ ps
HPK50	245 V	$61 \pm 3$	$(34 \pm 3)$ ps

# CMOS LGADs: the approach

- Try to exploit available **opportunities** and optimise **resources**
- Add gain layers and process splits to the already funded **ARCADIA mask-set**
- Optimise sensor performance by changing only relevant parameters (**short loops**)
- Be fully compatible with a (very) standard **CMOS process**
- First iterations on already purchased wafers: **thicker substrates**, not fully optimised for timing, but good enough to **tune** the full **machinery**

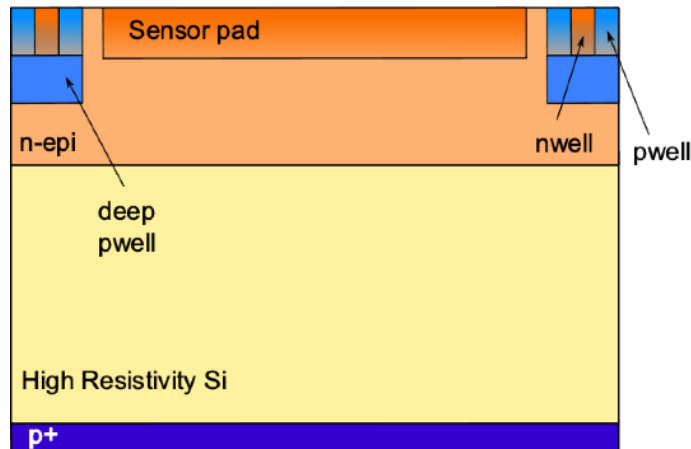




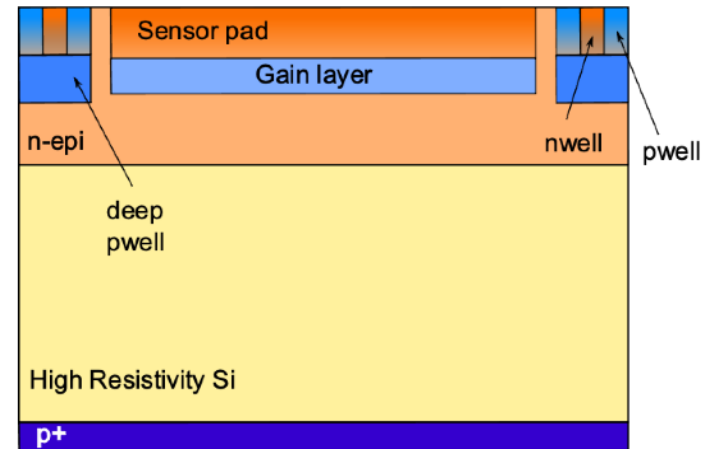
# CMOS LGADs: the concept

- Addition of a **simple gain** layer and patterned **termination structures**
- The deep-pwell separates the pixels and host the front-end electronics
- HV on the top: **AC coupling** to the front-end
- Both **active** and passive test structures

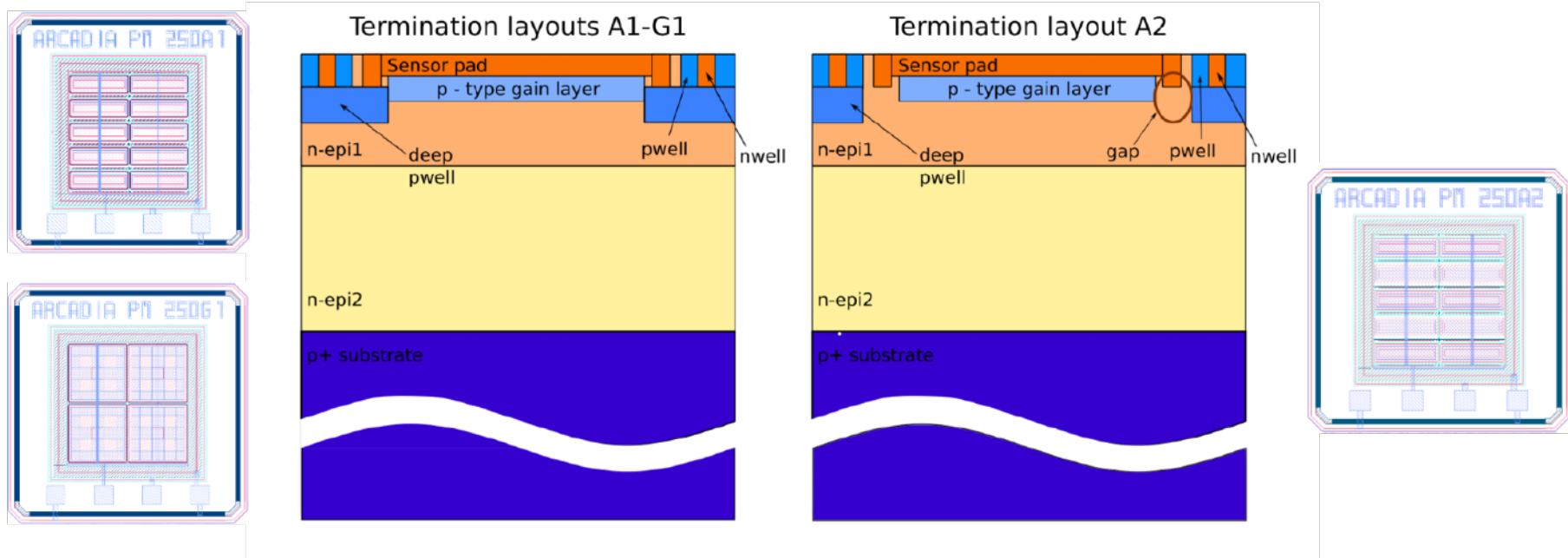
ARCADIA pad sensor



ARCADIA pad sensor with gain



## Test devices: junction termination

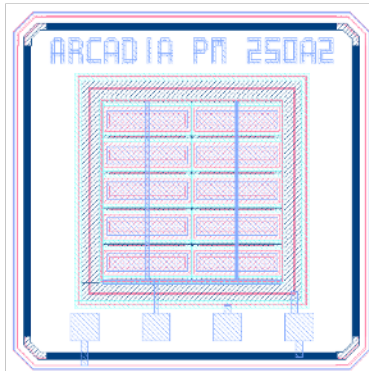
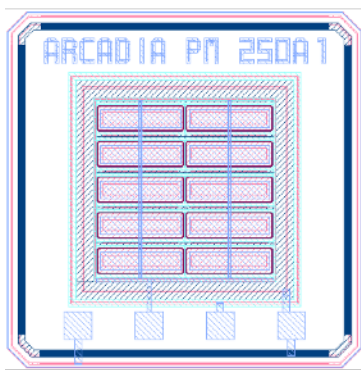
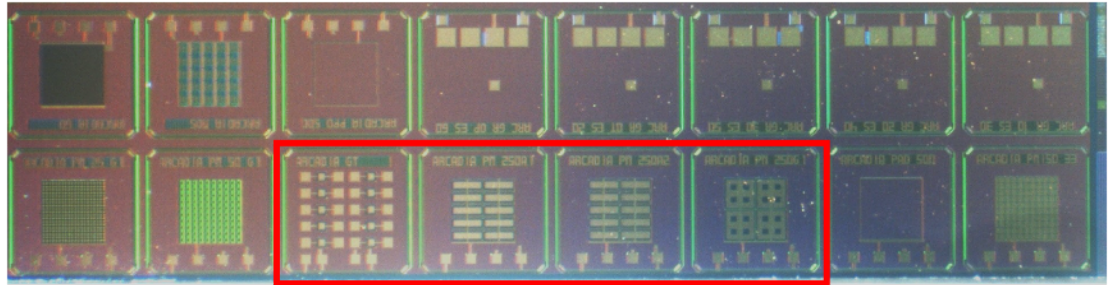


deep pwell below the junction termination:  
electrons generated below the deep pwell  
reach the gain layer

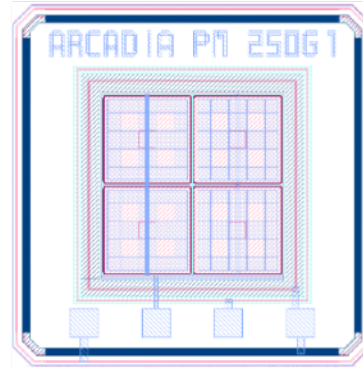
Termination directly facing the active region:  
electrons generated below termination can  
be collected without gain

# CMOS LGADs: passive test structures

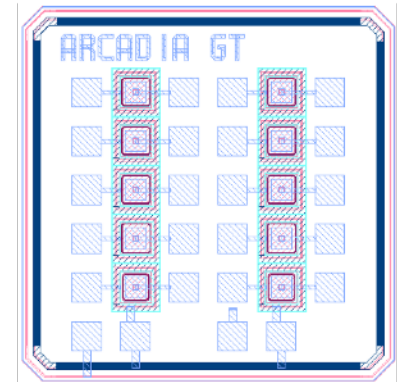
- Probe station testing
- External preamp



A1 and A2: Rectangular passive pads  
active area  $250\mu\text{m} \times 70\mu\text{m}$   
(same geometry as in active pixel array)



Square passive pads with large  
fill factor:  $250\mu\text{m} \times 250\mu\text{m}$

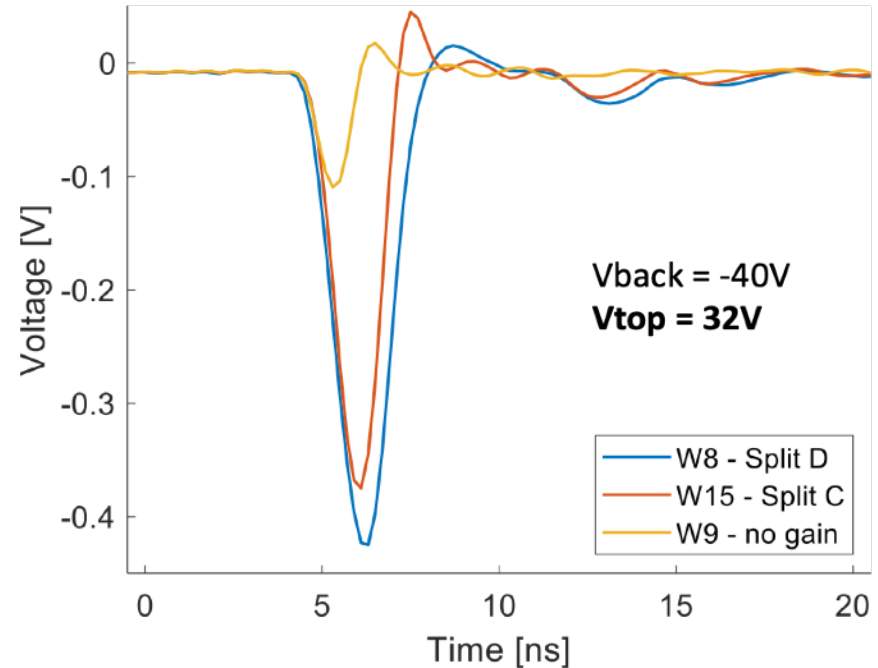
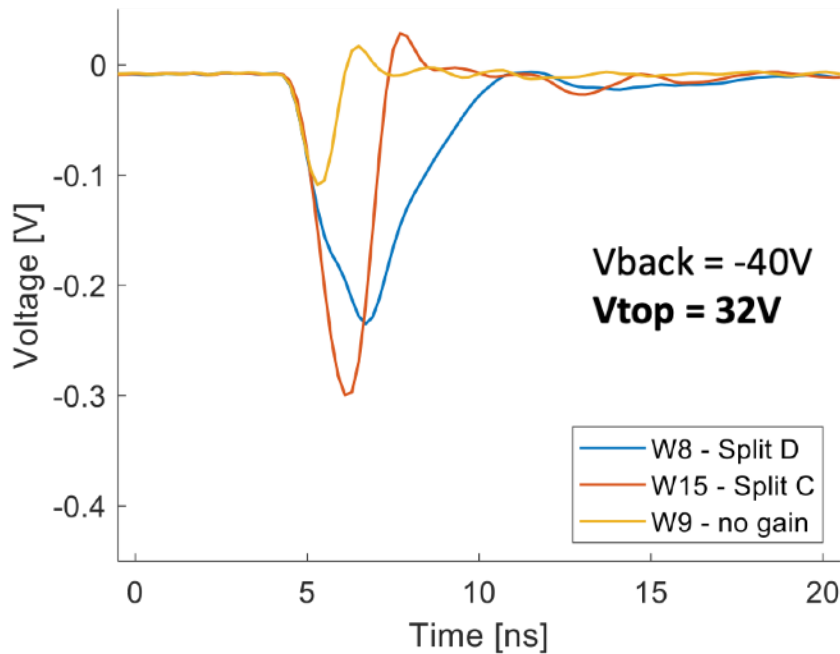


Test pads with variations of  
Guard Ring geometry

# We have gain!

<https://indico.cern.ch/event/1415726/contributions/6144007/attachments/2942716/5170665/>

[Pancheri ALICE UpgradeWeek 8Oct2024 v2.pdf](#) - L. Pancheri

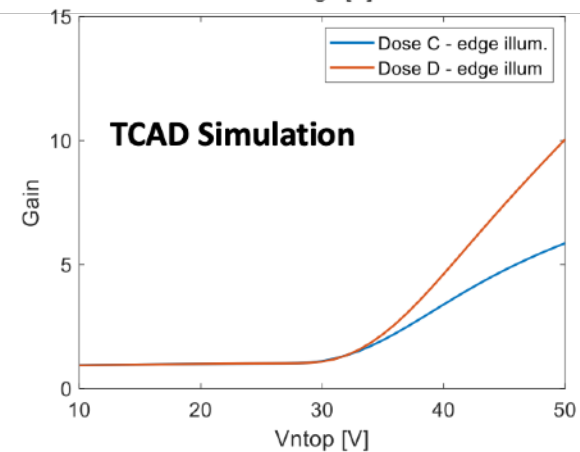
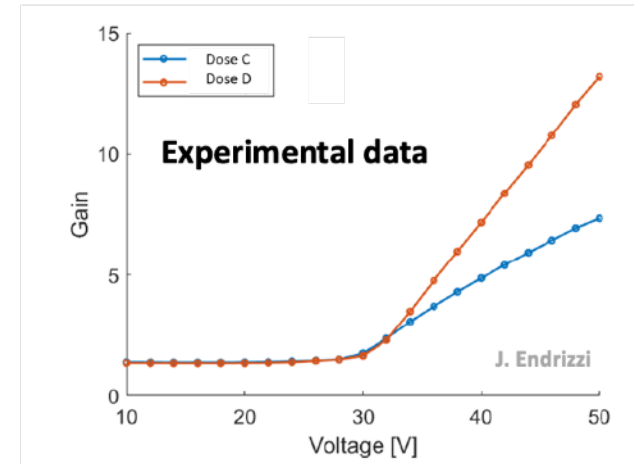
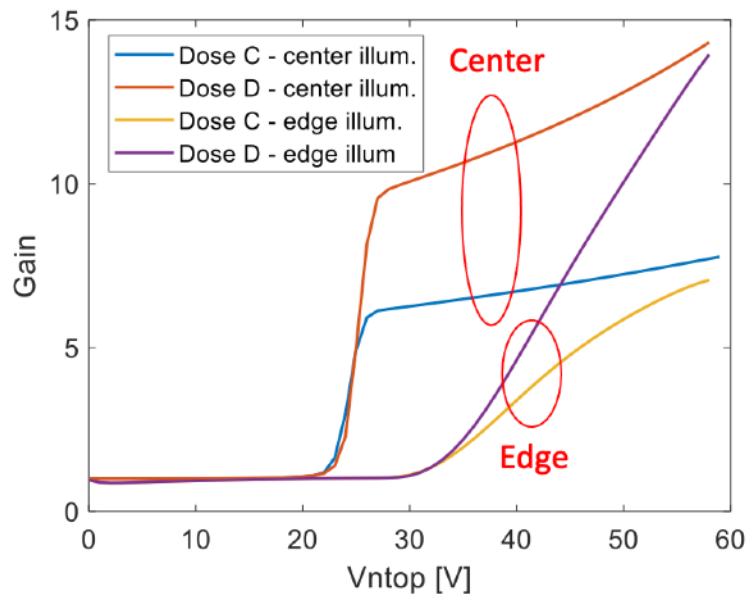


Jacopo Endrizzi

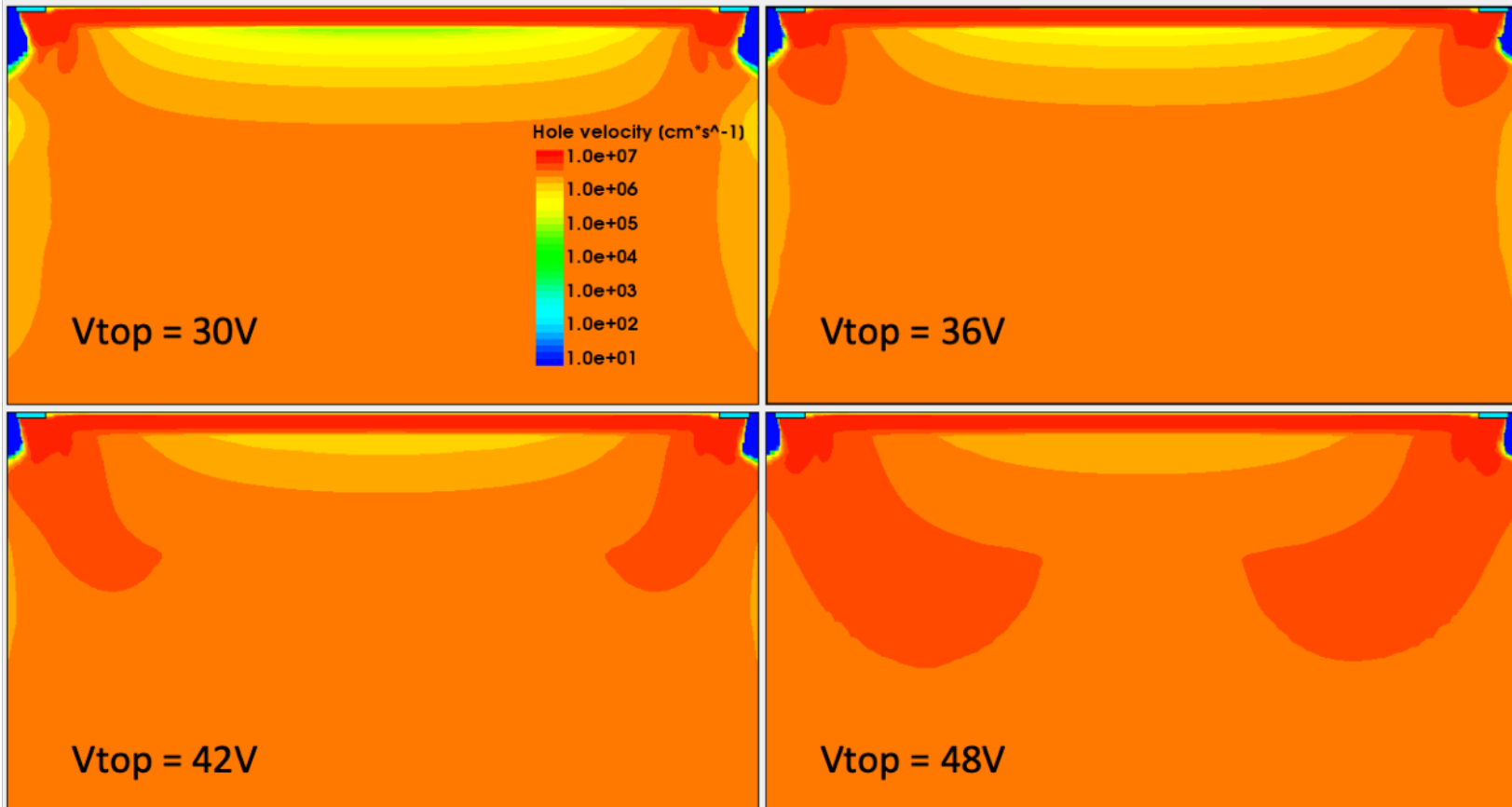
- In first short loop gain was 2.5x: gain layer to be optimised
- So far between 5 and 15, depending on the split
- Much better matching with simulations

## Quasi-static characterization: A2 gain with NIR LED illumination

- In **device A2** the high-field region expands laterally with voltage: onset of gain at larger Voltage.
- High voltage: 55 – 60V → Gain is similar to central value

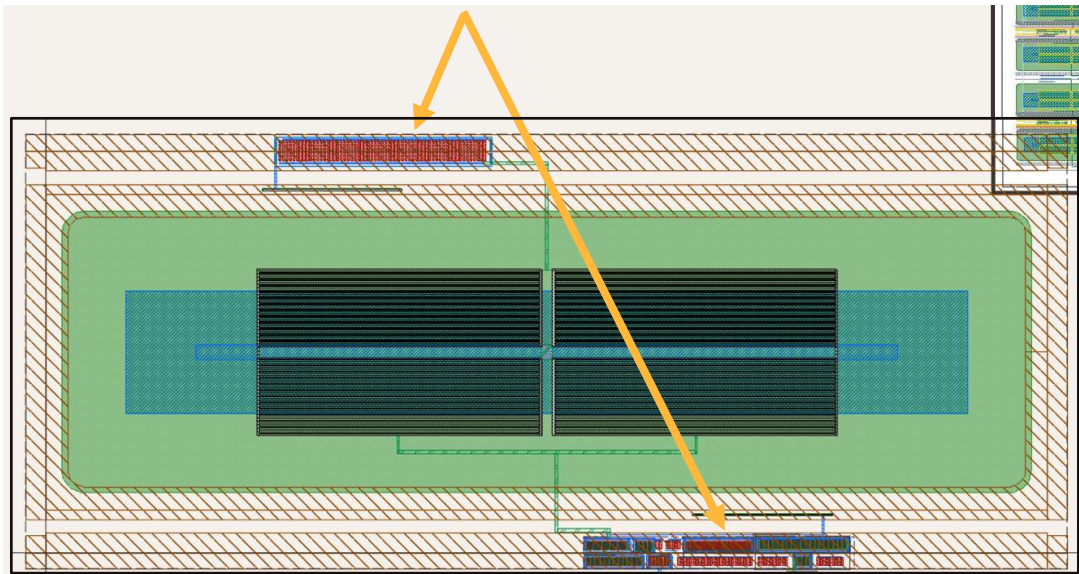
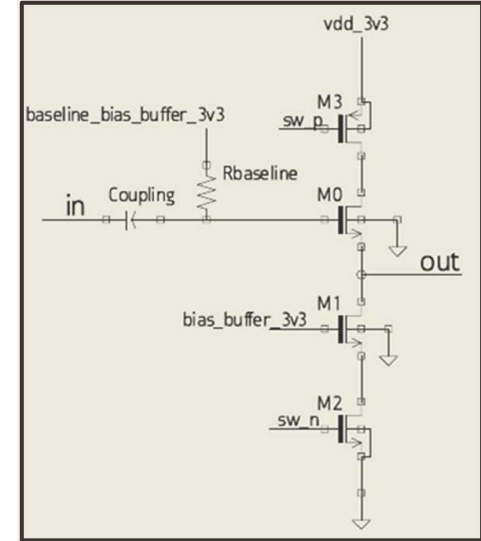
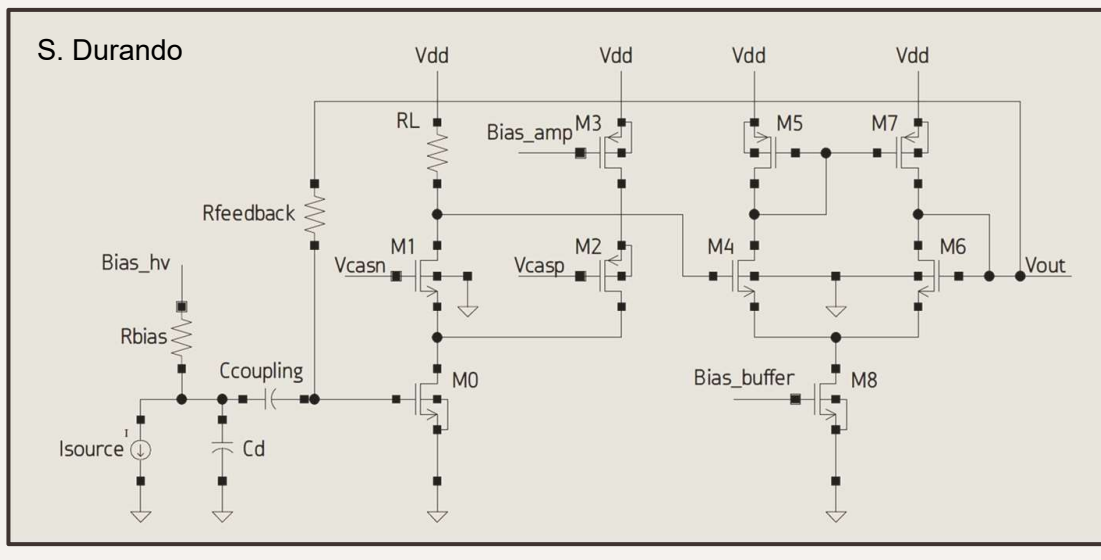


# The effect of the top voltage



























# CMOS LGADs with front-end: first concept

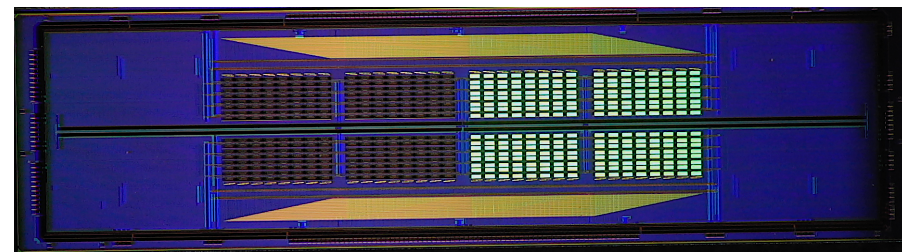
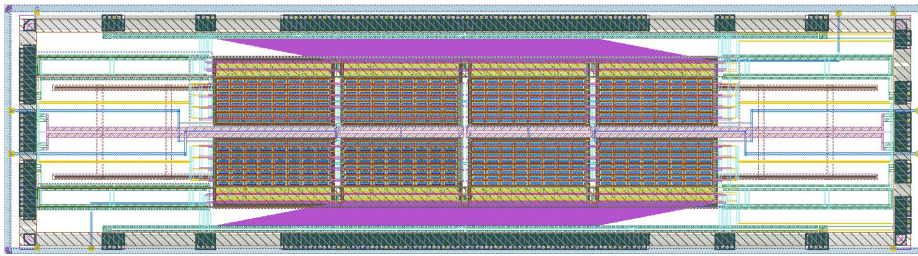


- Front-end included in the pixel
- Similar to FE for standard LGAD
- Limit on RX coverage to be relaxed in dedicated runs

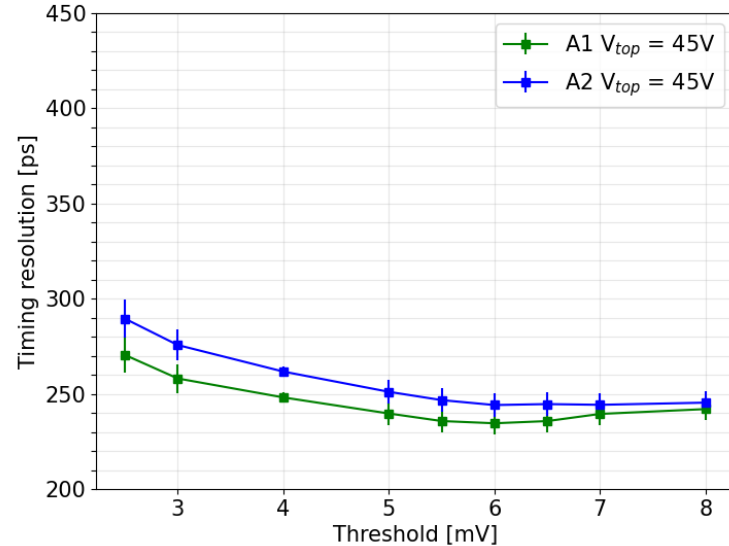
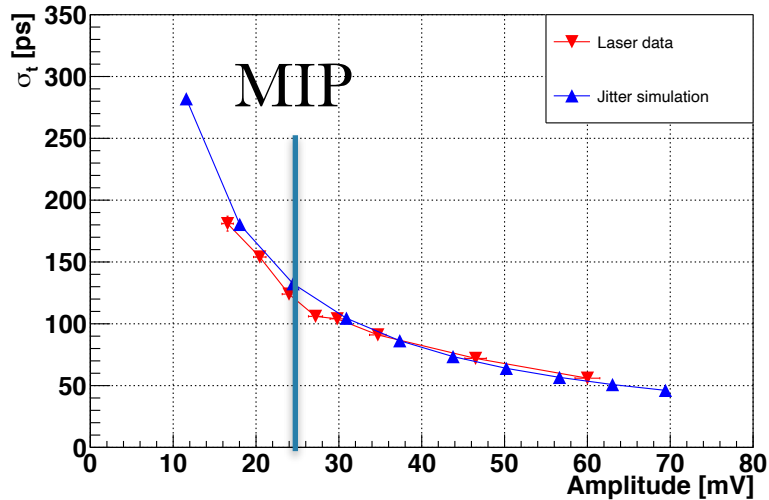


## First results on monolithic CMOS detector with internal gain

U. Follo <sup>a,b,\*</sup> G. Gioachin <sup>a,c,\*</sup> C. Ferrero <sup>a,b</sup> M. Mandurrino <sup>a</sup> M. Bregant <sup>d</sup>  
S. Bufalino <sup>a,c</sup> F. Carnesecchi <sup>e</sup> D. Cavazza <sup>f</sup> M. Colocci <sup>f,g</sup> T. Corradino <sup>h,i,1</sup>  
M. Da Rocha Rolo <sup>a</sup> G. Di Nicolantonio <sup>j</sup> S. Durando <sup>a,b</sup> G. Margutti <sup>j</sup> M. Mignone <sup>a</sup>  
R. Nania <sup>f</sup> L. Pancheri <sup>h,i</sup> A. Rivetti <sup>a</sup> B. Sabiu <sup>f,g</sup> G.G.A. de Souza <sup>d</sup>  
S. Strazzi <sup>f,g</sup> and R. Wheadon <sup>a</sup>



# CMOS LGADs with front-end: results from first short loop



- Gain: 2.5x
- Estimated jitter for 1 MIP with laser: 130 ps
- Obtained resolution in beam test with nominal parameters significantly worse: sensor-related effect

# CMOS LGADs: matching simulation and measurements

Introduction

Design

Chip Characterization

Conclusions

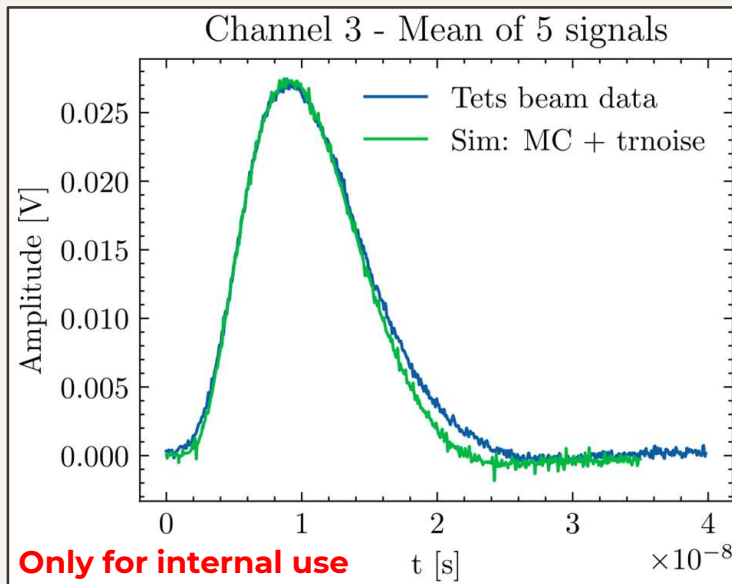
## Simulation matching

First production:  
sensor gain  $\approx 2.5$

MonteCarlo simulation  
of the sensor

Transient noise  
simulation of the  
electronics

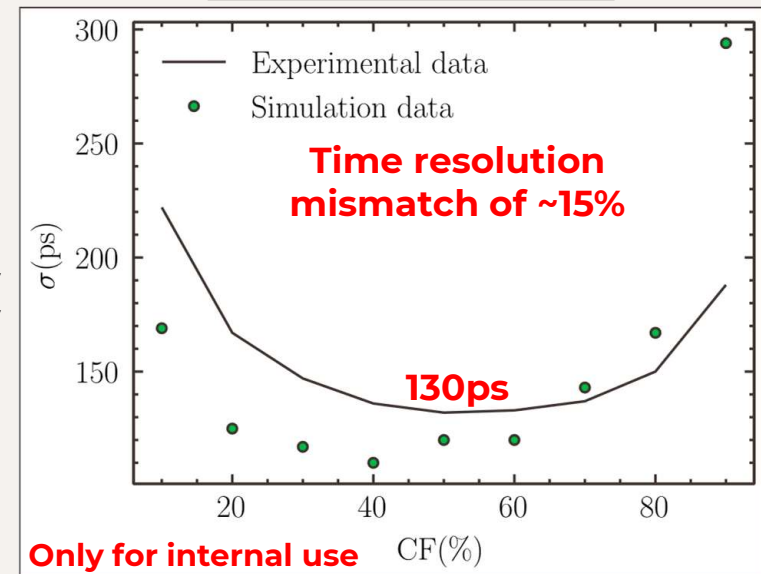
Comparison of  
simulation results and  
experimental data



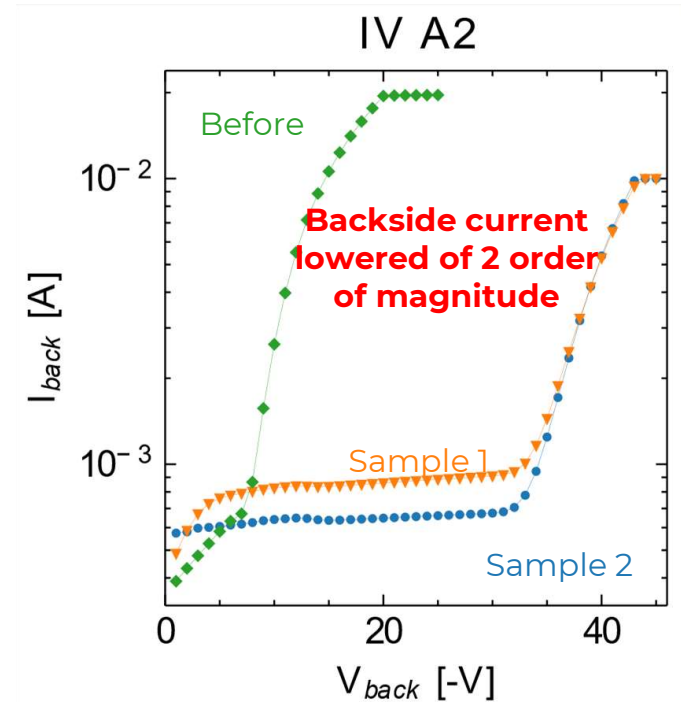
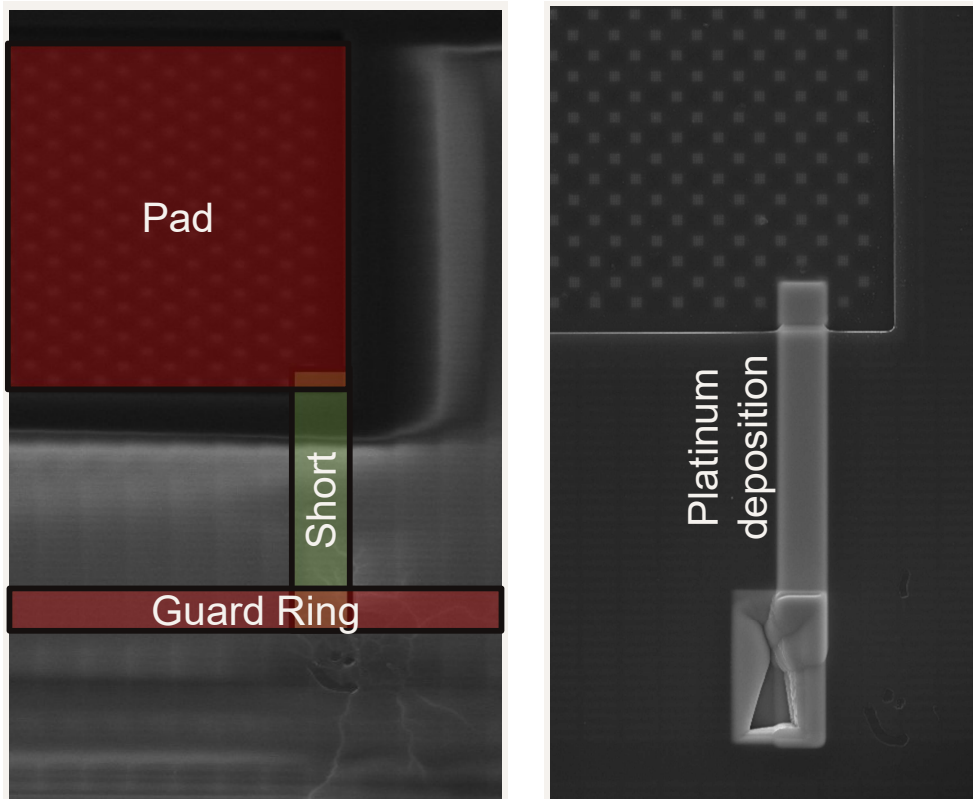
Test beam data:  
TOP  $\rightarrow$  61V  
BACK  $\rightarrow$  -15V

Simulation:  
TOP  $\rightarrow$  45V  
BACK  $\rightarrow$  40V

More precise  
comparison after  
next test beam  
with FIB sensors



- 14 • Different set of experimental parameters to match simulated results



- Backside current reduced by two order of magnitudes with FIB
- FiB done at National Institute for Metrology Research (INRiM) in Torino



# CMOS LGADs with front-end: new short loop with higher gain

Introduction

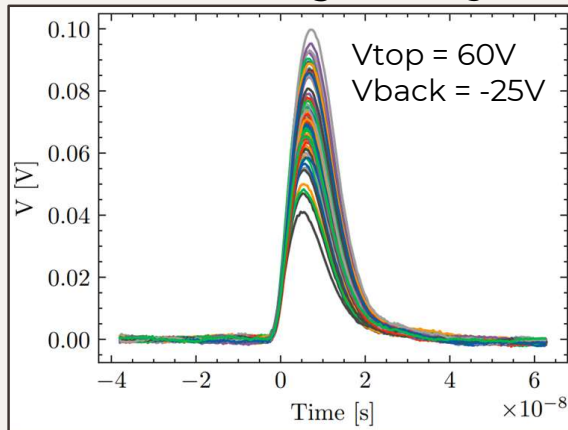
Design

Chip Characterization

Conclusions

## Fe55 - New production

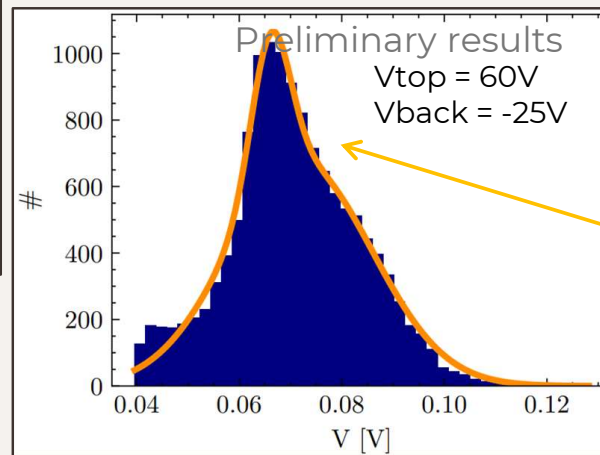
First estimation of **gain** using a non collimated radiation source of Fe55



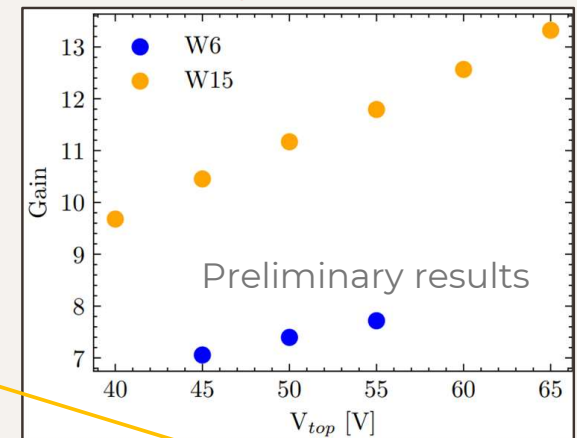
$X_K$		Energy (keV)	Relative probability
K $\alpha_2$		5,88772	51
		5,89881	100
K $\beta_1$	}	6,49051	20,5
		6,5354	

Superposition of  $K_\alpha$  and  $K_\beta$

Amplitude distribution in response to Fe55



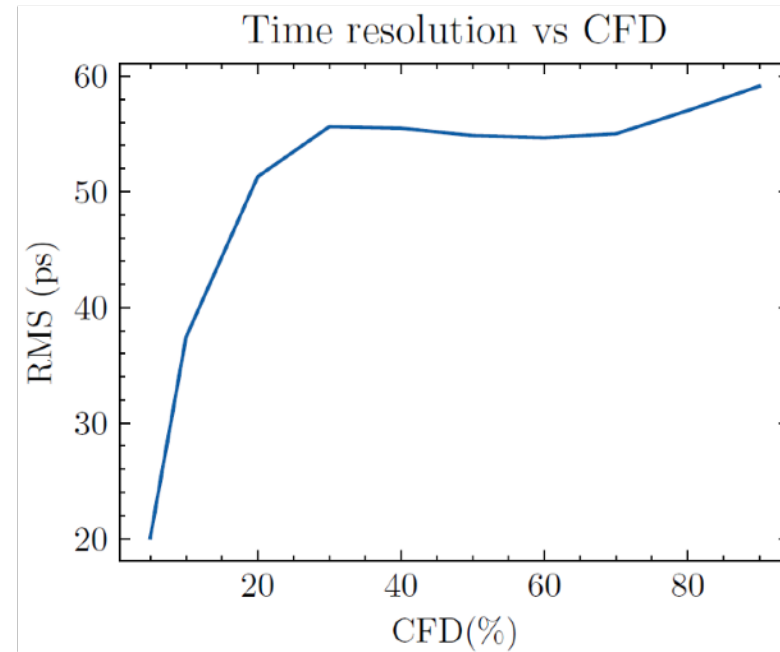
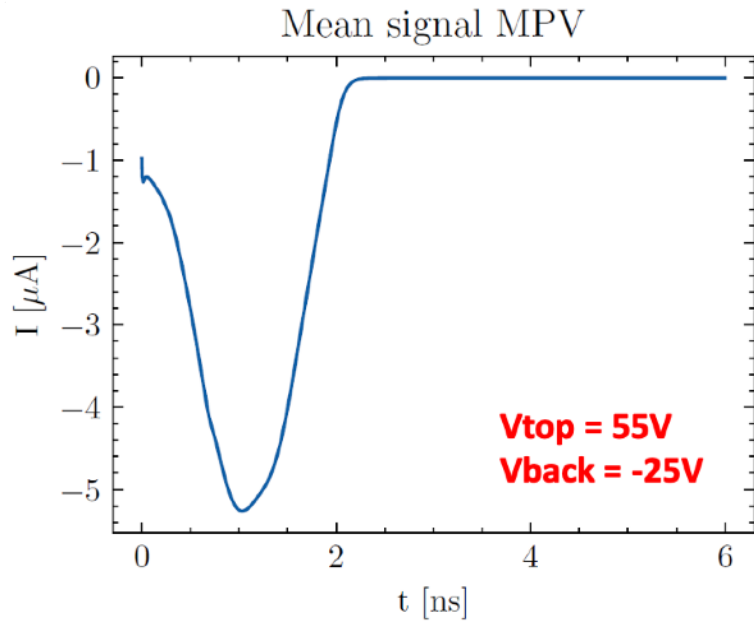
Fist gain estimation



$$Gain = \frac{Peak [V/e]}{Electronics_{gain} [V/e]}$$

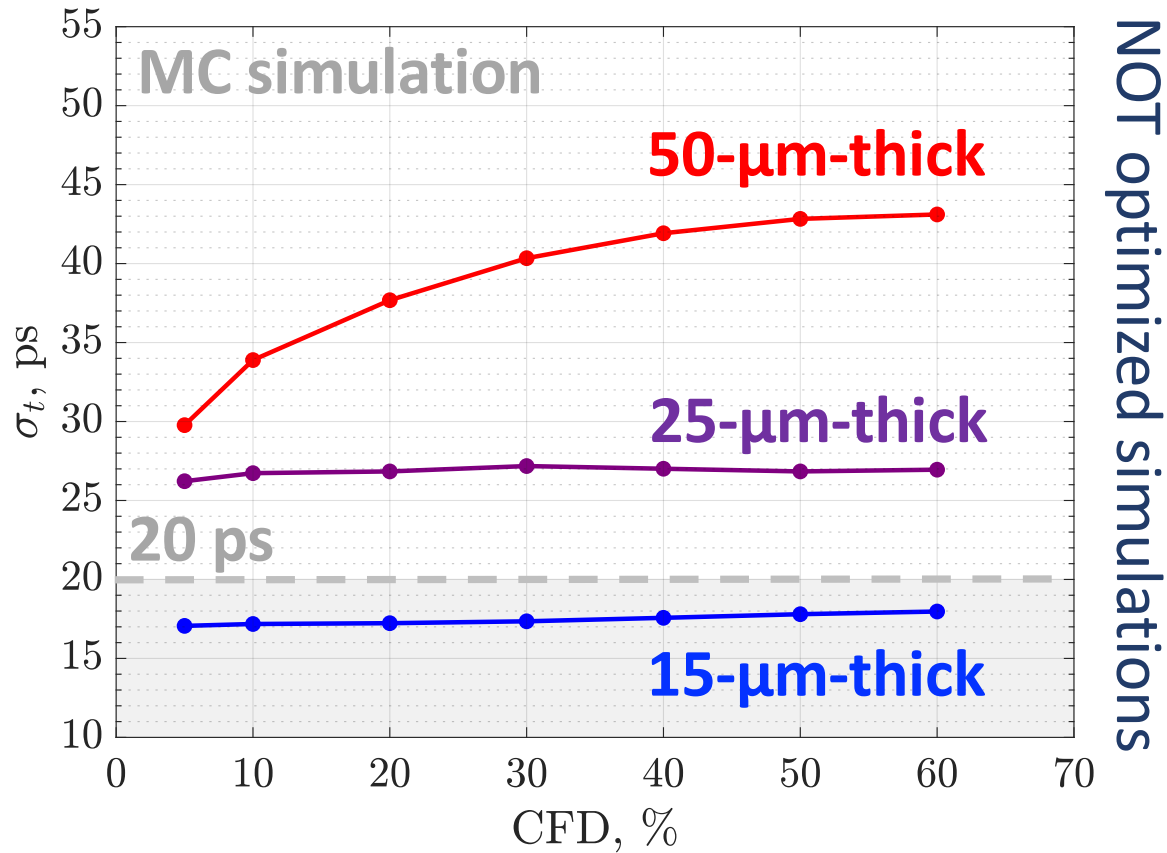
From electronics simulations matched with data

# How much resolution could we get now...



- Beware of border effect!

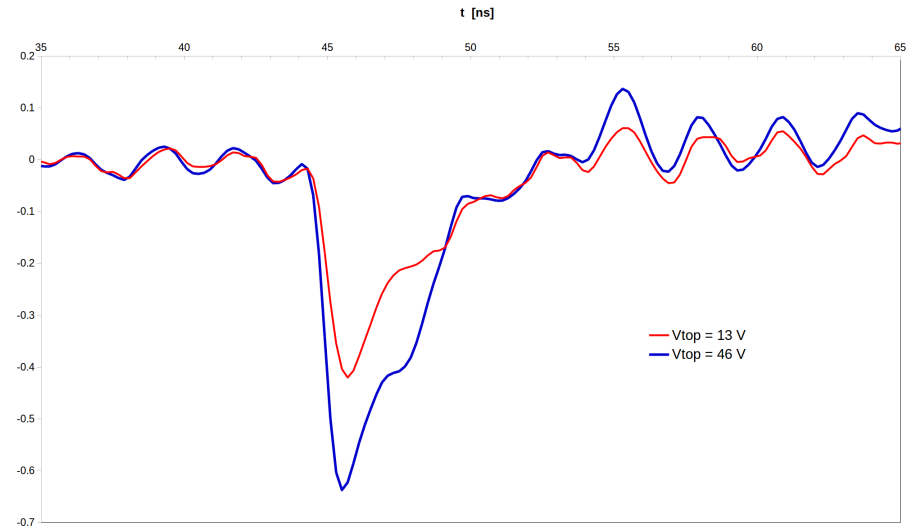
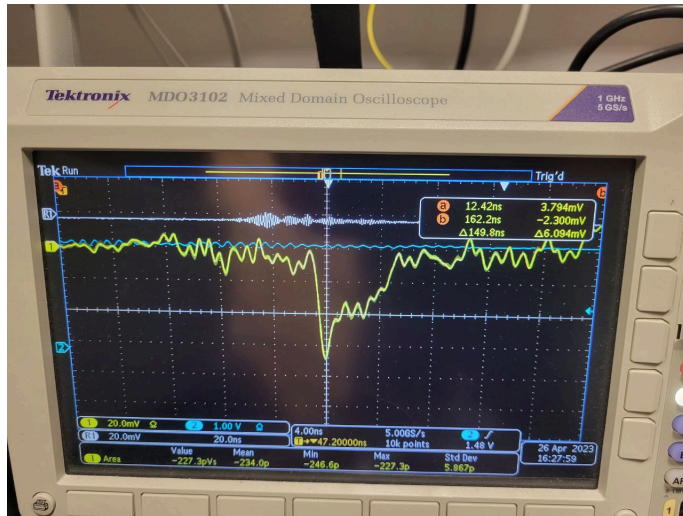
# ...and in the next short loops?



- Beware of border effect!



# Back to May 23...



- $V_{top} = 40$  V
- $V_{back} = 160$  V
- $V_{Ngr} = 8$  V
- $f_{laser} = 100$  Hz
- Signal Amplitude =  $120 \mu A$
- Signals acquired with 1 structure:  
Wafer 5 - 250 A1 (W5\_250\_A1A2\_A1)
  - Rising time  $\simeq 1 \div 1.5$  ns
  - Signal duration  $\simeq 6$  ns
  - Increasing  $V_{top}$  the signal amplitude increases
- First delivered structure are the 200  $\mu m$  thick option: worse set for timing!
- 50  $\mu m$  thick structure expected soon

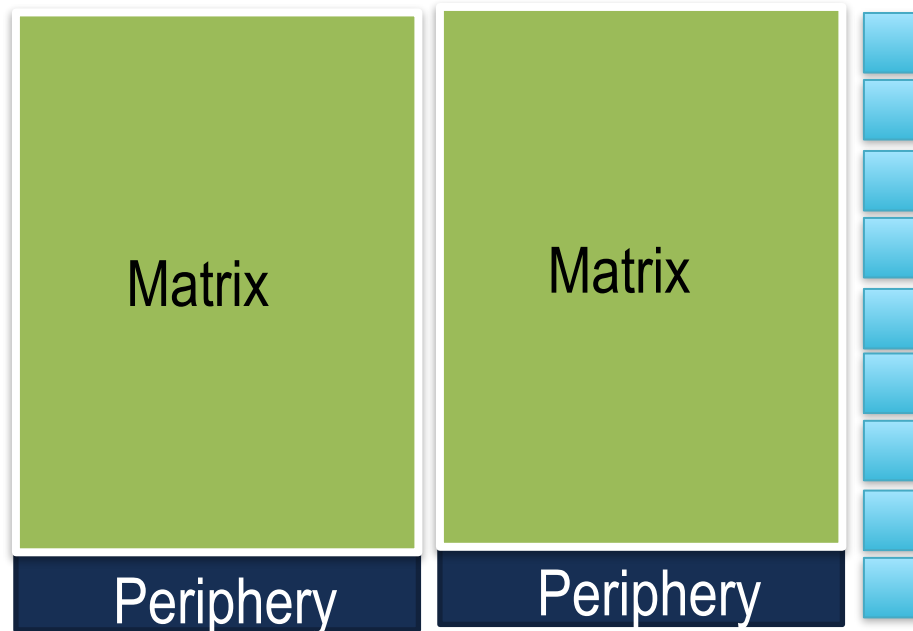
• L. Pancheri, S. Durando

# Next steps



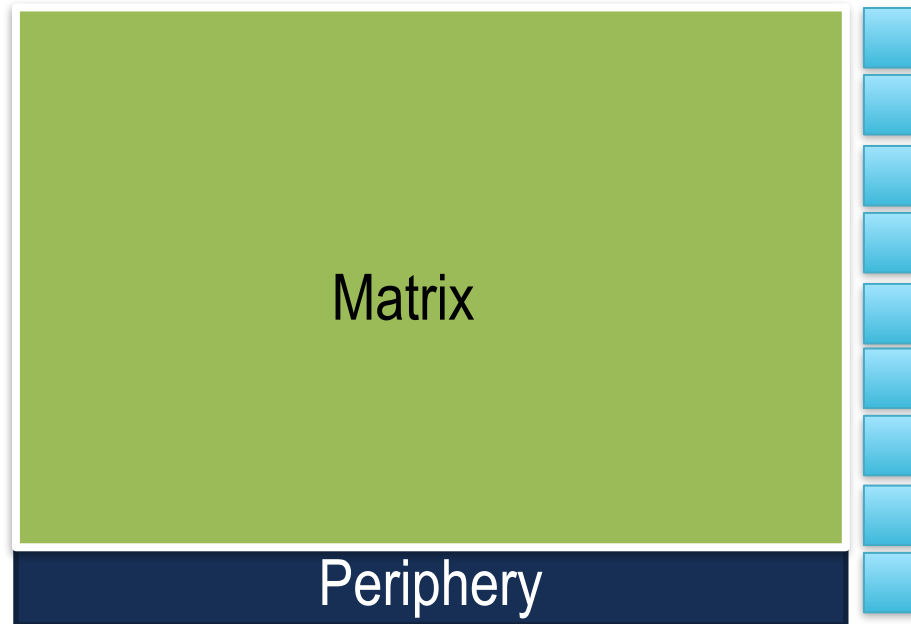
- We have CMOS sensors with embedded front-end and gain
- A very **good progress** in a relatively **short time**
- Test beam (October 24) and simulations activities to match **measurements** and **simulations**
- One short loop with thin active area (first or second quarter 2025) to further improve the **time resolution** by using **thinner** active substrate
- Full sensor optimisation and ultimate time resolution can **not** be **achieved** without a **full set of dedicated masks**
- This will be the **last short loop** which makes sense with the **ARCADIA** mask-set
- After that we need to move to **dedicated engineering run**

# Next engineering runs: ER1



- Larger test chips contains all what is needed in the final version (including testability:-))
- Unit must be uniformly repeatable in view of the final sensor
- **Pixel size** defined to optimise **timing**
- Keep the **matrix** as simple as possible and the **periphery** versatile
- Large chips can accommodate a **reasonable** (2-3) number of **different flavours**

# Next engineering runs: ER2



- Final, **full-reticle** sensor design
- Only one sensor and electronics option
- Assembled with mostly already silicon proven blocks
- **Pre-production** run

# Next engineering runs: ER3



- **It might not be needed, but HAS TO BE IN THE BUDGET!**
- Things could be also fixed in “short-loops”
- Stitching?

# Stitching?



<https://cerebras.ai/product-chip/>

The screenshot shows the Cerebras website homepage. At the top left is the Cerebras logo. The navigation menu includes "Products", "Solutions", "Developers", "Company", and "Resources". A "Contact Us" button is in the top right. The main content area features a large heading "The future of AI is Wafer-Scale" and a sub-heading "Cerebras' third-generation wafer-scale engine (WSE-3) is the fastest AI processor on Earth. It surpasses all other processors in AI-optimized cores, memory speed, and on-chip fabric bandwidth." Below this is a "WSE-3 Datasheet" button. On the right side of the page is a photograph of a person in a white lab coat holding a large, square, gold-colored wafer with a grid of small, circular components.

- **24 cm x 24 cm, 2,7 Trillions transistors, stiched processor for AI in 7 nm...**
- **Cost is accordingly...**

- We **have** CMOS LGADs with **gain!**
- Development done at very **low-cost so far...**
- ...but there is a **minimum threshold** you can not go below!
- Next imminent steps: beam test, simulation tuning, final short loop
- In the next months: consolidate design, mechanics/integration, read-out teams...i.e. the full project!
- The less is done, but let's be optimistic and carry on!